

AMENDMENTS TO THE CLAIMS

Please amend the claims to read as follows:

1 - 7 (cancelled)

8. (original) A capacitor comprising:

a lower electrode formed on a substrate, wherein the lower electrode includes a metal pattern, and a layer comprising Pt covering an upper surface and sidewalls of the metal pattern, and wherein the metal pattern is formed of a material capable of forming a conductive oxide;

a dielectric layer formed on the lower electrode; and

an upper electrode formed on the dielectric layer.

9. (original) The capacitor as recited in claim 8, further comprising a seed layer comprising Pt between the substrate and the metal pattern.

10. (original) The capacitor as recited in claim 9, wherein the metal pattern is formed comprising a metal selected from the group consisting of Ru and Ir.